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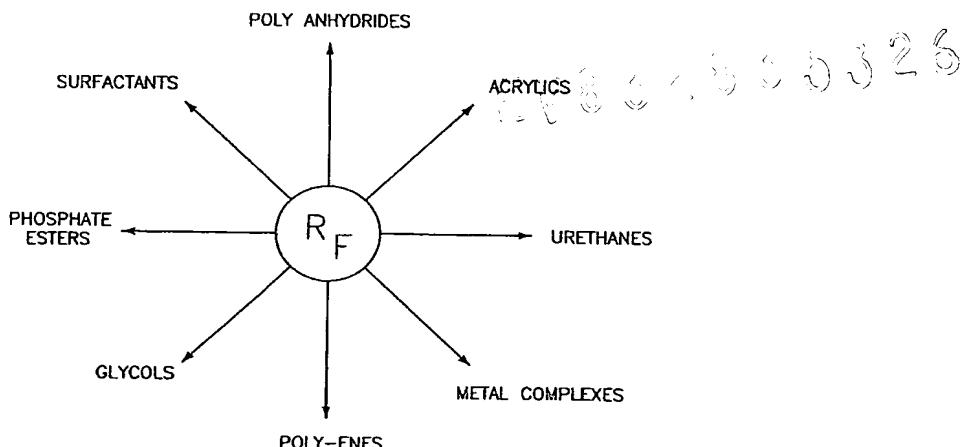
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(54) Title: PRODUCTION PROCESSES AND SYSTEMS, COMPOSITIONS, SURFACTANTS, MONOMER UNITS, METAL COMPLEXES, PHOSPHATE ESTERS, GLYCOLS, AQUEOUS FILM FORMING FOAMS, AND FOAM STABILIZERS



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(57) Abstract: Production processes and systems are provided that include reacting halogenated compounds, dehalogenating compounds, reacting alcohols, reacting olefins and a saturated compounds, reacting reactants having at least two -CF₃ groups with reactants having cyclic groups. R_F-compositions such as R_F-intermediates, R_F-surfactants, R_F-monomers, R_F-monomer units, R_F-metal complexes, R_F-phosphate esters, R_F-glycols, R_F-urethanes, and/or R_F-foam stabilizers. The R_F portion can include at least two -CF₃ groups, at least three -CF₃ groups, and/or at least two -CF₃ groups and at least two -CH₂- groups. Detergents, emulsifiers, paints, adhesives, inks, wetting agents, foamers, and defoamers including the R_F-surfactant composition are provided. Acrylics, resins, and polymers are provided that include a R_F-monomer unit. Compositions are provided that include a substrate having a R_F-composition thereover. Aqueous Film Forming Foam ("AFFF") formulations are provided that can include R_F-surfactants and/or R_F-foam stabilizers are provided.



European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Declarations under Rule 4.17:

- *as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii)) for all designations*
- *as to the applicant's entitlement to claim the priority of the earlier application (Rule 4.17(iii)) for the following designations AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VC, VN, YU, ZA, ZM, ZW. ARIPO patent (BW, GH, GM, KE, LS, MW, MZ,*

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